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## (54) NEGATIVE TYPE PHOTOSENSITIVE COMPOSITION, NEGATIVE TYPE PHOTOSENSITIVE PLANOGRAPHIC PRINTING PLATE AND ITS DEVELOPING METHOD

## (57)Abstract:

PURPOSE: To obtain a negative type photosensitive compsn. which has excellent developability with an aq. alkaline without contg. an org. solvent, has a good inking property and has sufficient plate wear by incorporating a specific alkali- soluble high-polymer compd. into this compsn.

CONSTITUTION: This photosensitive compsn. contains the alkali-soluble high- polymer compd. having 10 to 40mol% phenolic hydroxyl group-contg. unit of an acid value of ≤100. More preferably, the acid value of the alkali-soluble high-polymer compd. having 10 to 40mol% phenolic hydroxyl group-contg. unit is ≤300. Further preferably, the alkali-soluble high-polymer compd. having 10 to 40mol% phenolic hydroxyl group-contg. unit is a copolymer obtd. by copolymn. of the addition polymerizable monomer expressed by the formula and other addition polymerizable vinyl group-contg. monomer. In the formula, R1 denotes a hydrogen atom and methyl group, R2 denotes -COO-, -CONH-; (n)

$$CH_{\epsilon} = C (R^{*})_{ii} (DH)$$

denotes 0 or 1. The compd. described above preferably contains further a polymerizable compd. having an addition polymerizable unsatd, bond and a photopolynm, initiator.

## LEGAL STATUS

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